# ACT Node
# Standard Recipes

| Resist | ZEP 520A | Sample Prep for Resist spin | |
|---|---|---|---|
| Tone | Positive Tone Resist | Cleaning Solution | Sonicate |
| Solid content | 11% | Acetone | 2~5 min |
| Developer | ZED N50- (n Amyl Acetate) | IPA | 2~5 min |
| Stopper | ISO-Propanol | Ethanol (optional) | 2~5 min |
| Remover | ZDMAC- (Di-Methyl Acetamide) | DI Water Rinse | 2~5 min |
| Thinner | Anisole | Bake (Hotplate) | 5 min |

| Spin | Speed | Thickness | Time |
|---|---|---|---|
| | 4000rpm | 350~380nm | 60 s |
| **Pre-Bake** | **Temperature** | | |
| | 180 °C | if Hot Plate used | 2 min |
| | 180 °C | if oven used | 30 min |
| **Exposure** | **Voltage** | **Base Dose** | |
| | 20kV | 35 uC/cm2 | |
| **Develop** | ZEP Developer | Dipping | 1 min |
| **Stopper** | IPA | Dipping | 30 ~ 60 s |
| **Rinse** | DI water | Dip and Stir | 30 s |
| **Post Bake** | **Temperature** | before etch (if required) | |
| | 140 °C | Hot Plate | 2 min |
| | 140 °C | Oven | 25 min |
| **Remover** | ZEP Remover | Time depends on the patterns and thickness of resist | Soak for 30 ~ 40 min or more |
| | | DI Water rinse | 1 min |

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*Last Modified: 09/07/2020*